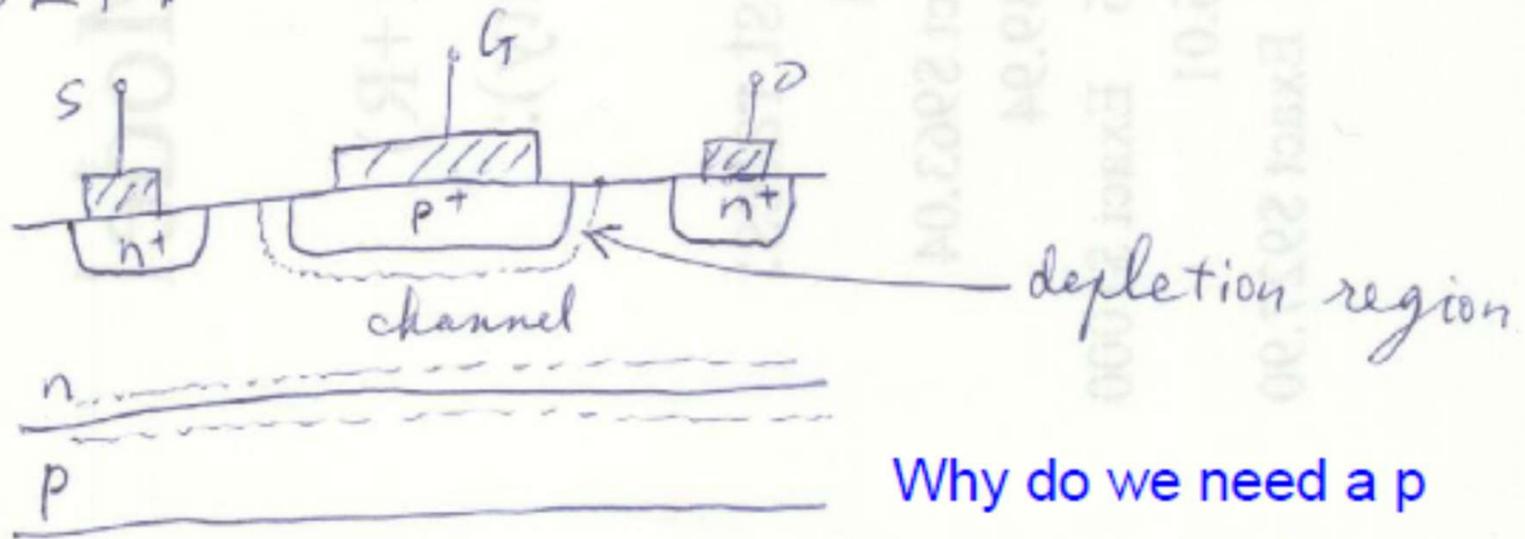


## Other types of FETs

- Si is the dominant semiconductor just because of the excellent Si/SiO<sub>2</sub> interface. So far, this is the best semiconductor/dielectric interface.
- But Si is inferior to many other semiconductors (e.g. GaAs, InSb, etc) in terms of  $\mu$ ,  $v_{sat}$ .
- RF, microwave, millimeter wave applications need faster transistors.
- But MOSFETs are not that good w/ those materials due to the lack of a good semiconductor/dielectric interface.

JFET

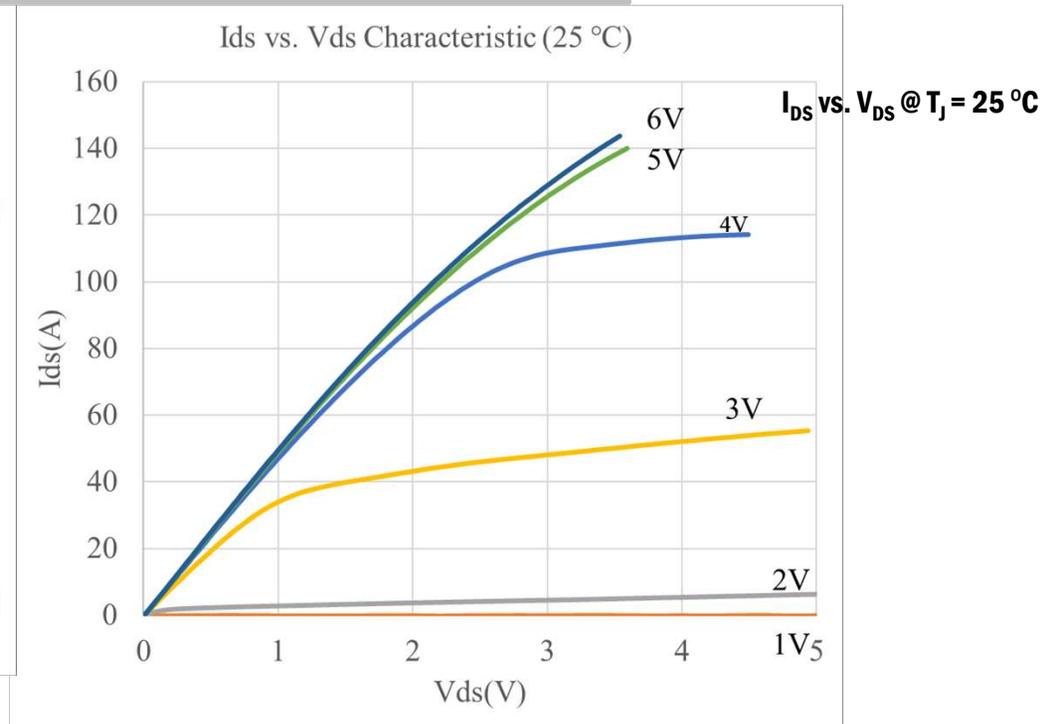
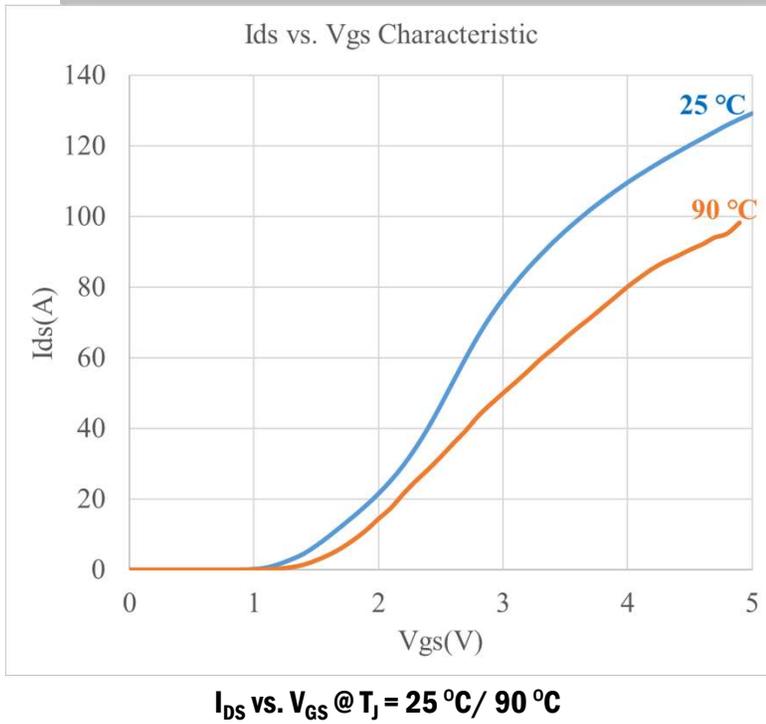
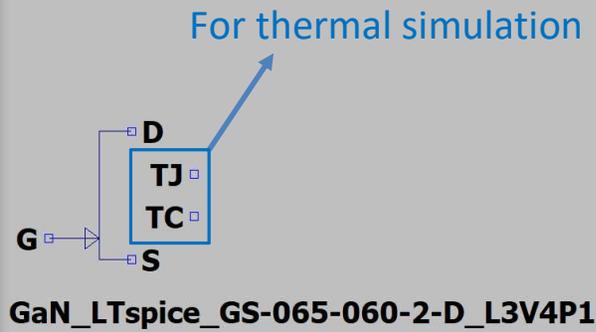
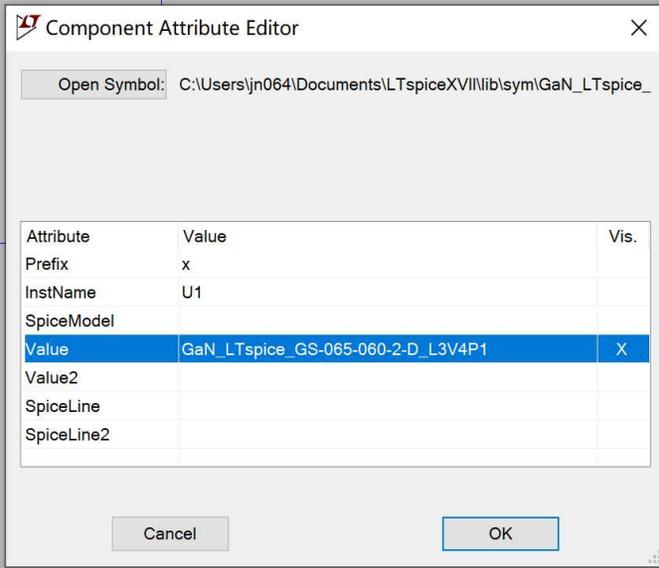


Why do we need a p substrate here?

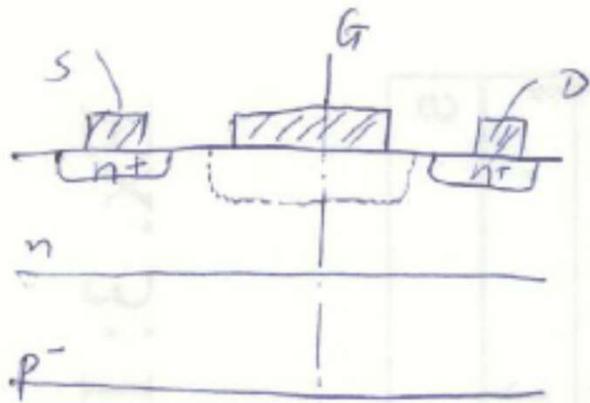
$V_{GS} < 0 \Rightarrow$  depletion region widens.  
At some point, the channel is off?

JFETs usually work in depletion mode (normally on).  
Enhancement mode (normally off) devices are desired for switches.

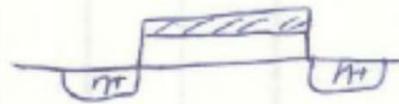
# GaN Die Model from manufacturer



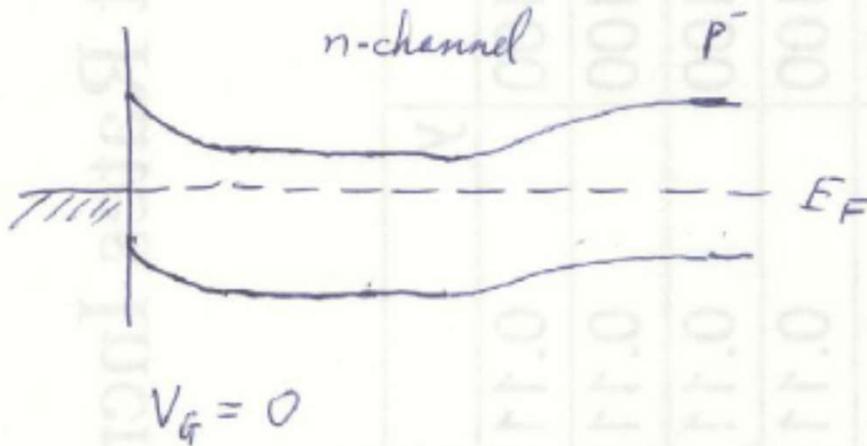
# MESFET

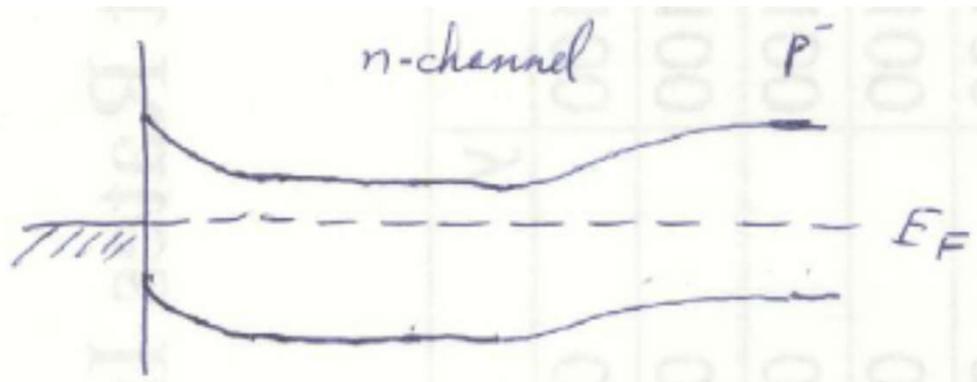


compare to MOSFET.  
no self alignment



↓ band diagram

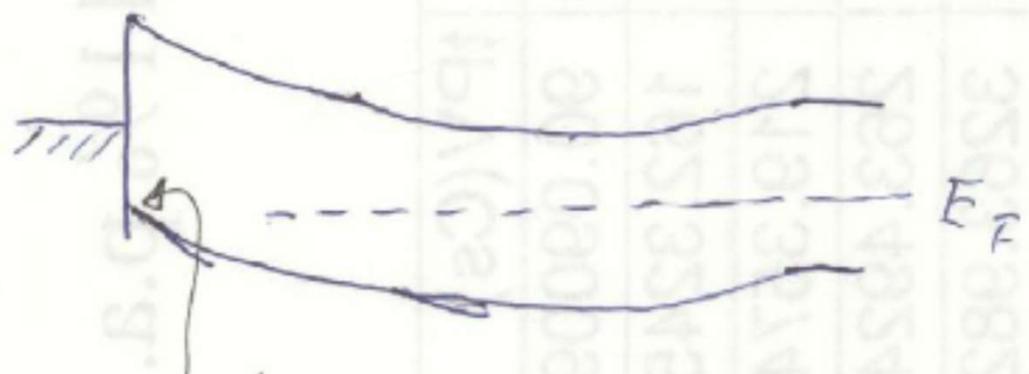




$V_G = 0$

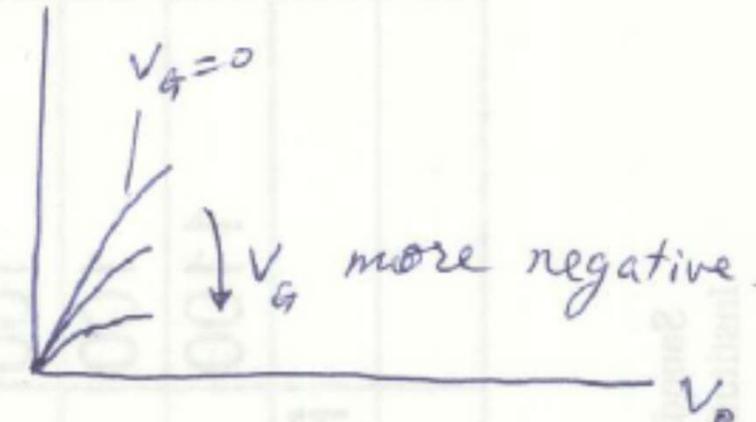
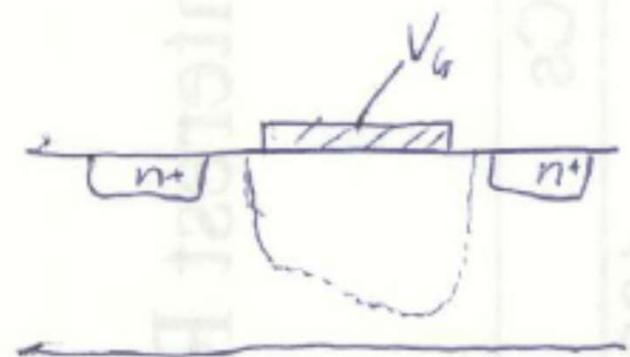
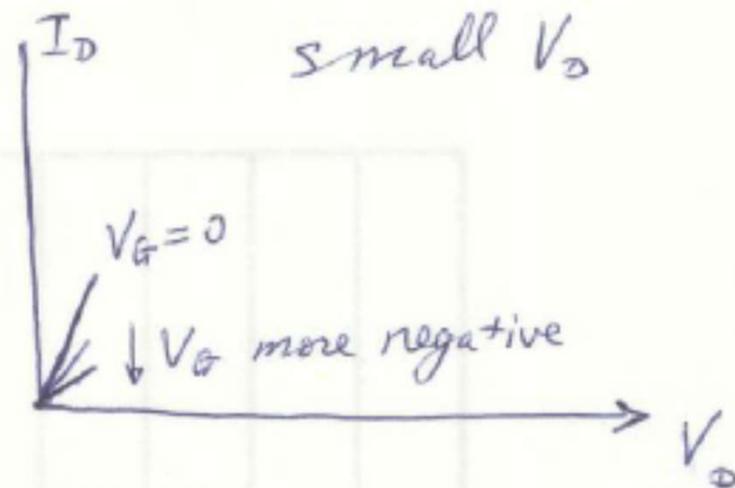
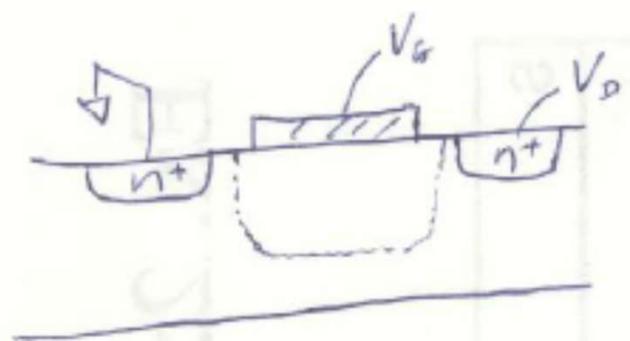


$V_G < 0$

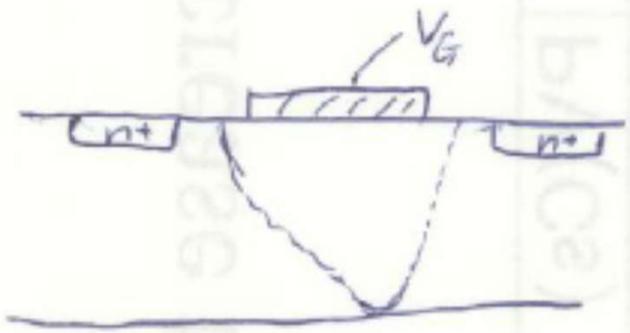


Will you have an inversion layer here?

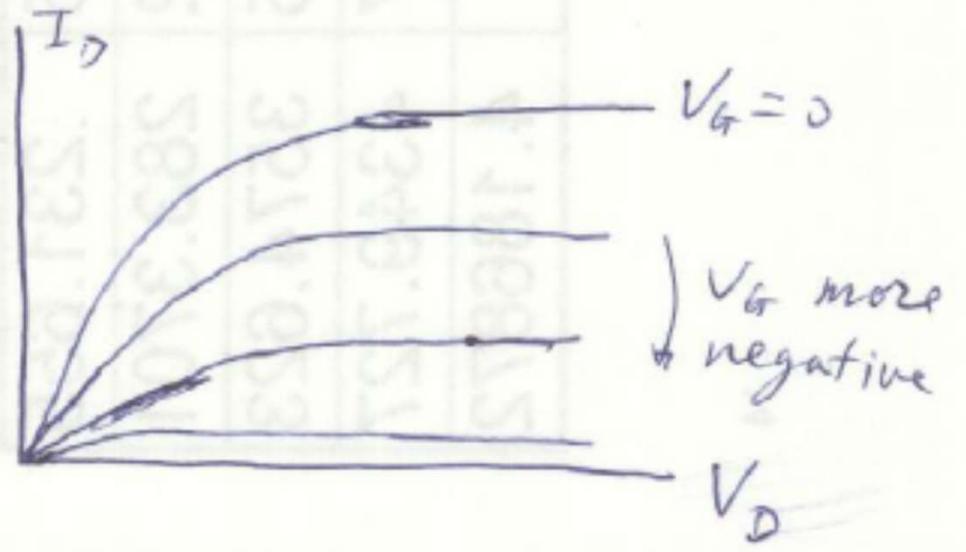
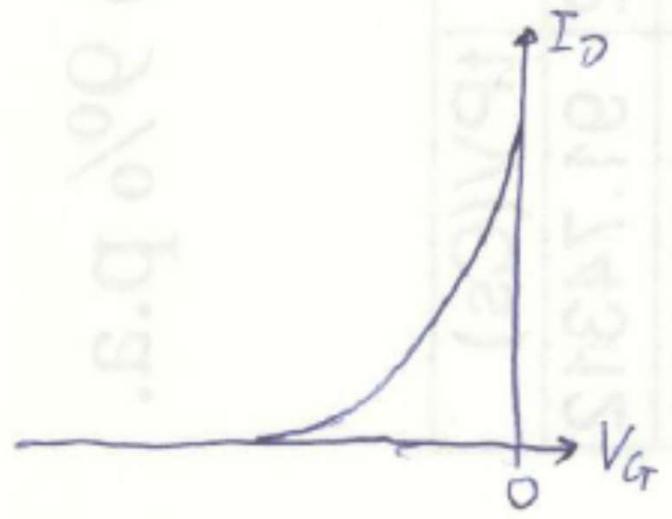
# I-V Characteristics



For larger (more positive)  $V_D$ ,  $V_G >$  more negative than  $V_{GS} \Rightarrow$  depletion region wider on the D side.



High  $V_D$ , pinch-off.  
saturation



"normally on"

JFETs & MESFETs are "normally on".

Channels are doped.

Turn them off by depleting them.

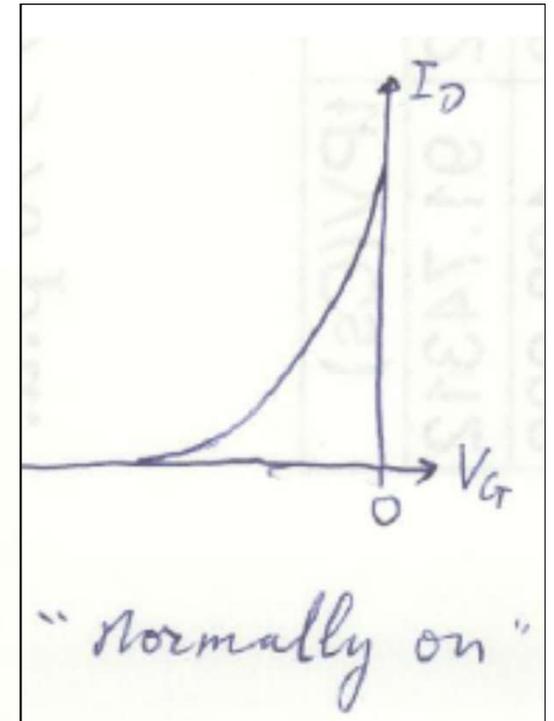
Dopants scatter carriers.

We want  $\mu$  &  $V_{sat}$  as high as possible.

(what's the mobility of a typical Si MOSFET?)

Solution: MODFET.

many names. HEMT, HFET

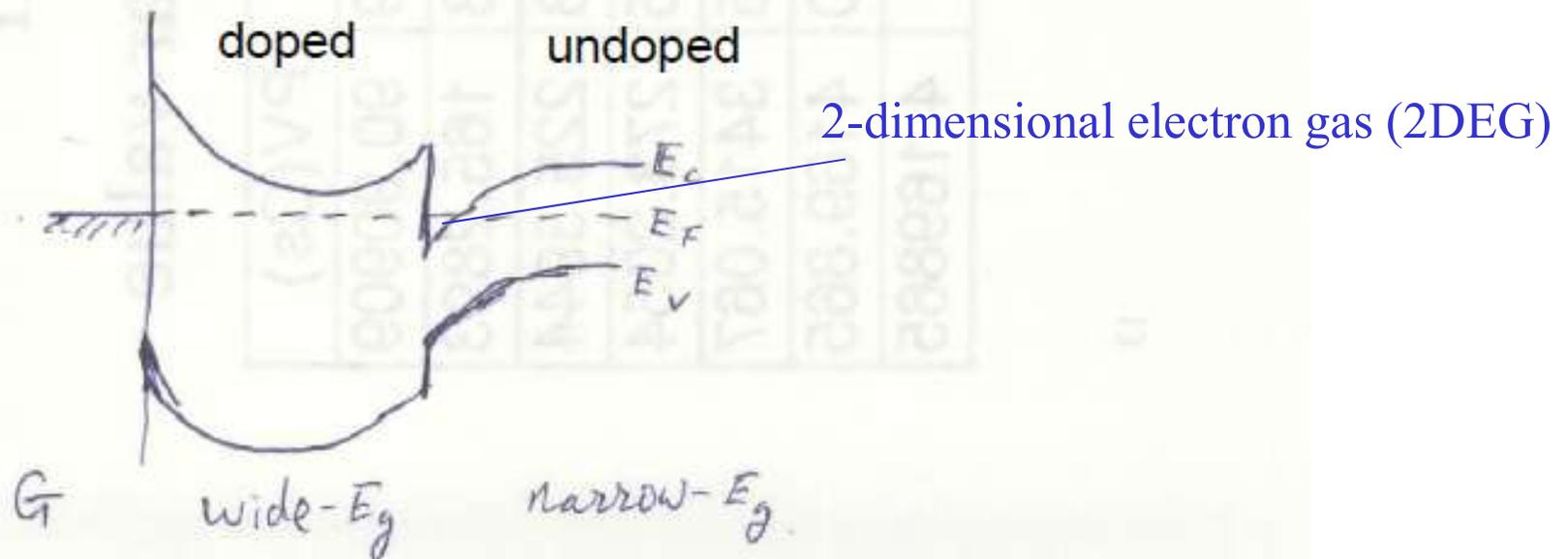


Solution: MODFET.

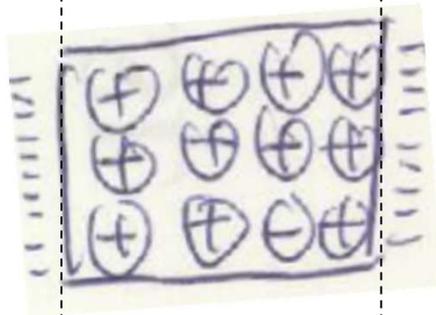
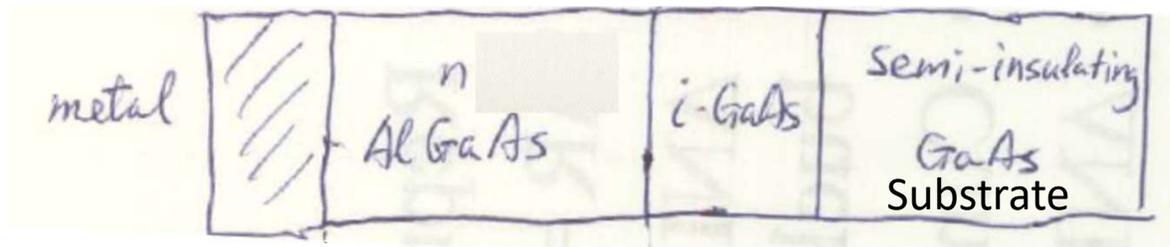
many names. HEMT, HFET

Want electrons ( $n$ ). but not dopants ( $N_D$ ).

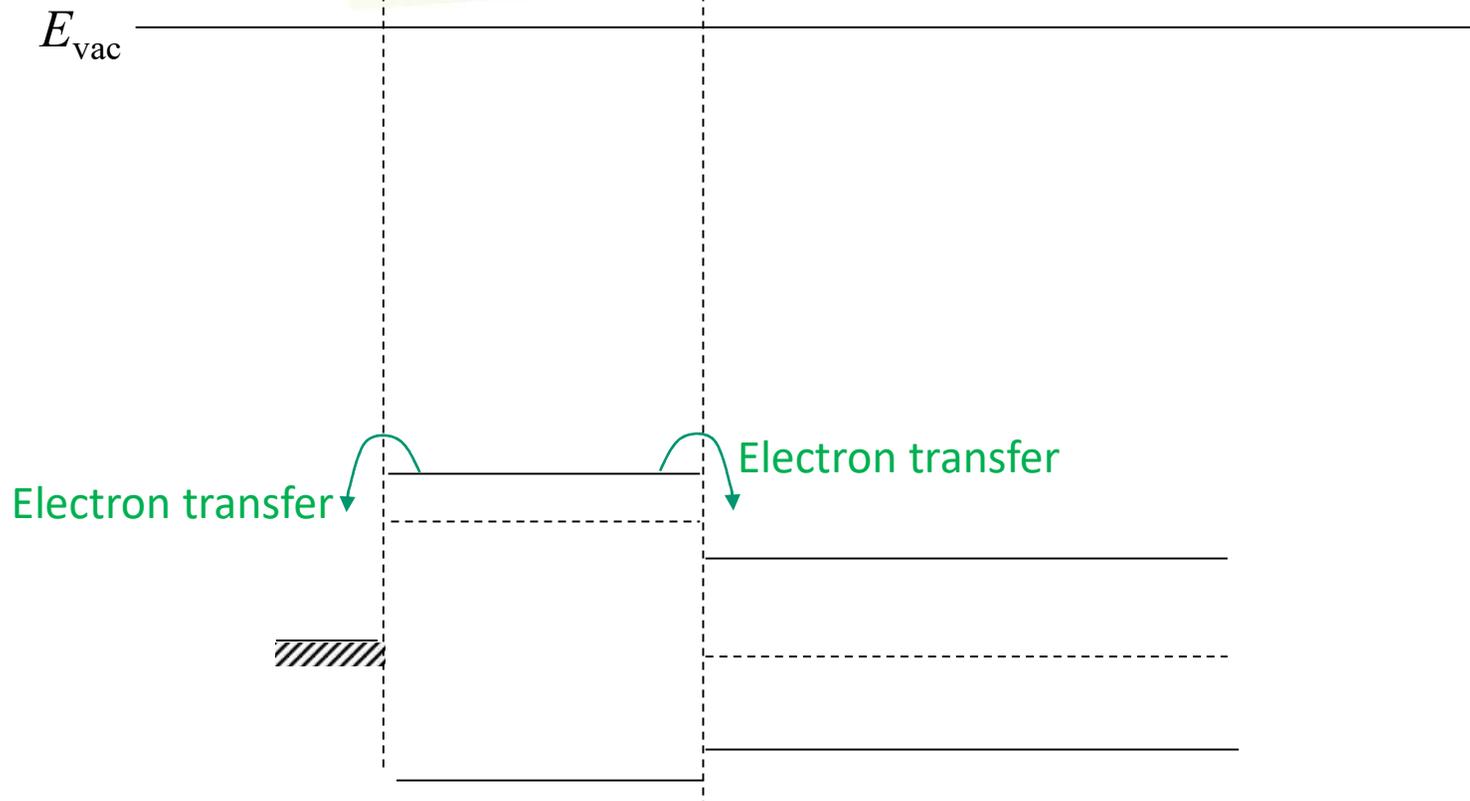
The idea: have  $N_D$  in one layer,  
but get  $n$  in another.

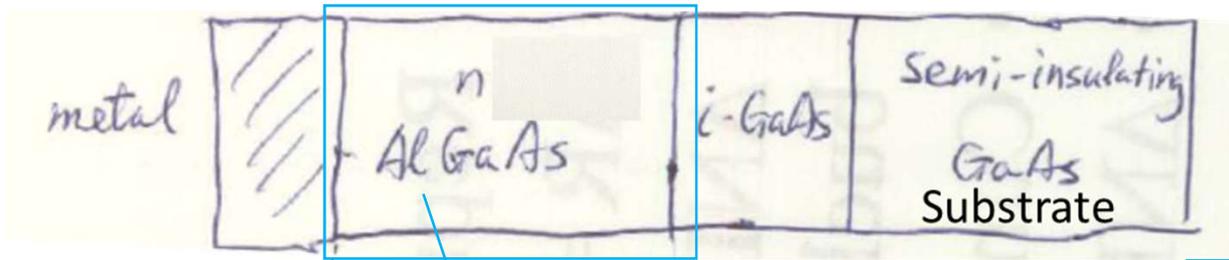


Recommended reading: Umesh & Singh, *Semiconductor Device Physics & Design*, p. 375 - 388

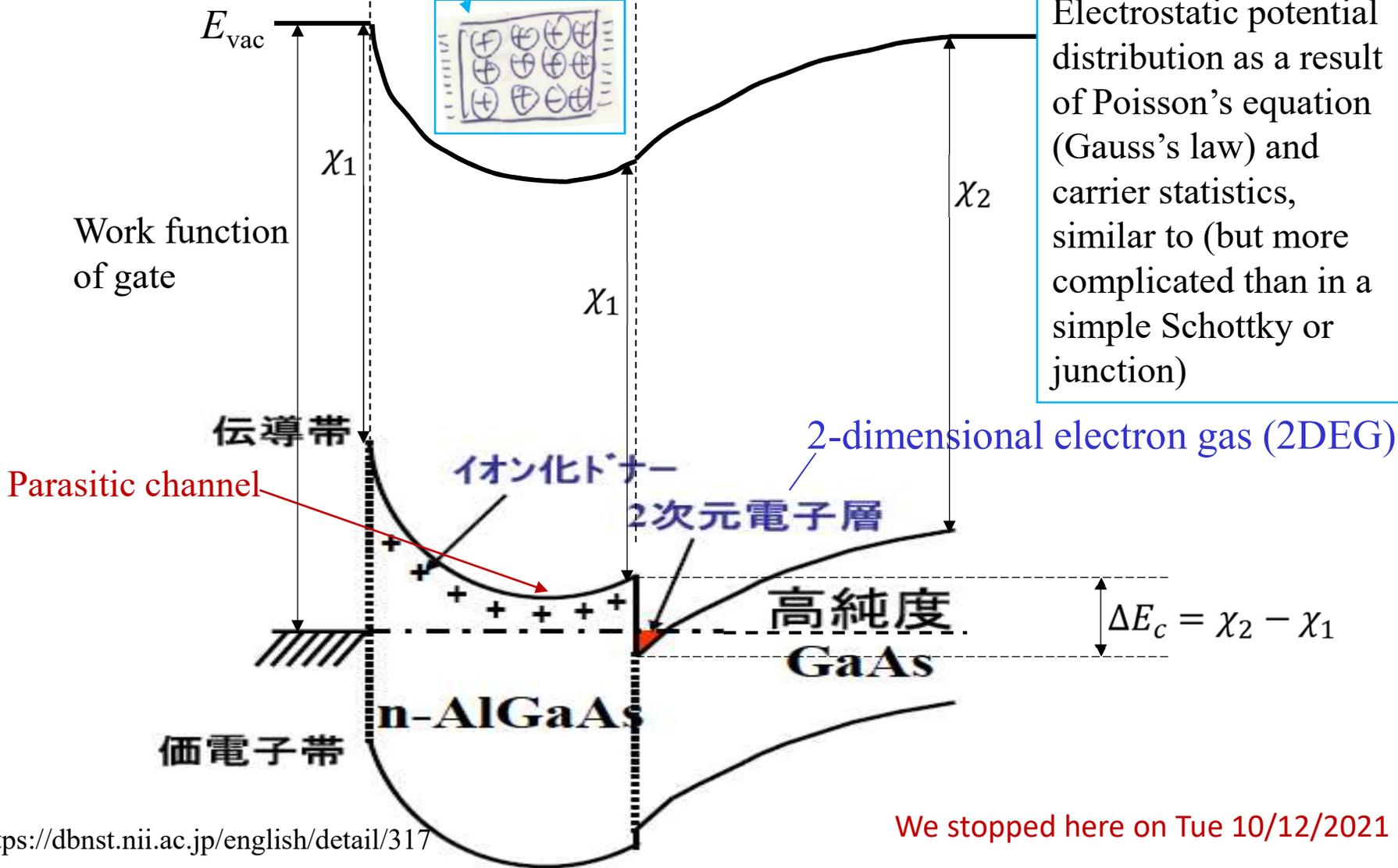


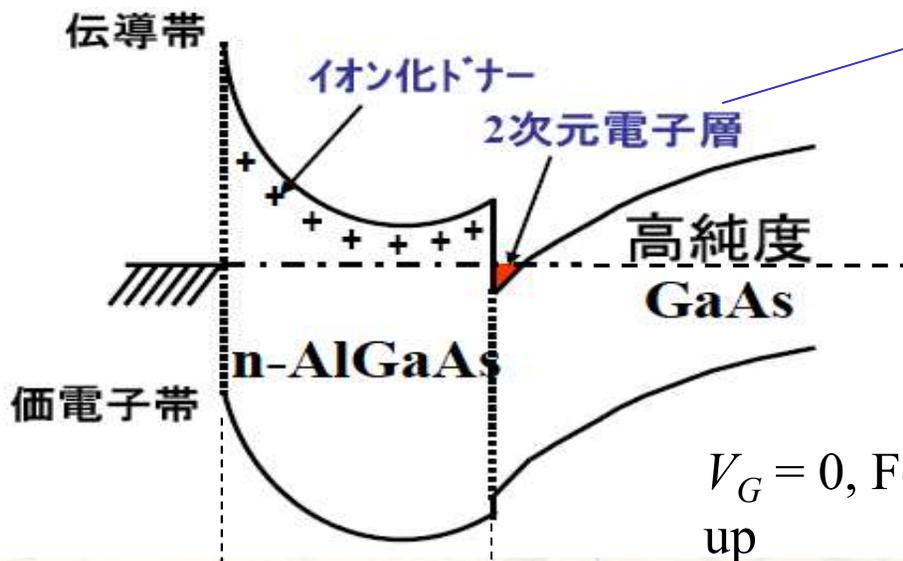
Space charge (ionizing donors) in AlGaAs **barrier layer** resulting from **electron transfer**



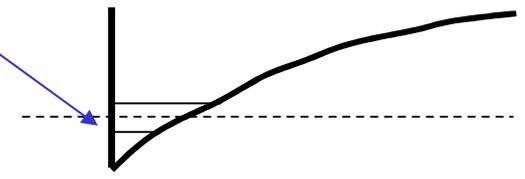


Electrostatic potential distribution as a result of Poisson's equation (Gauss's law) and carrier statistics, similar to (but more complicated than in a simple Schottky or junction)

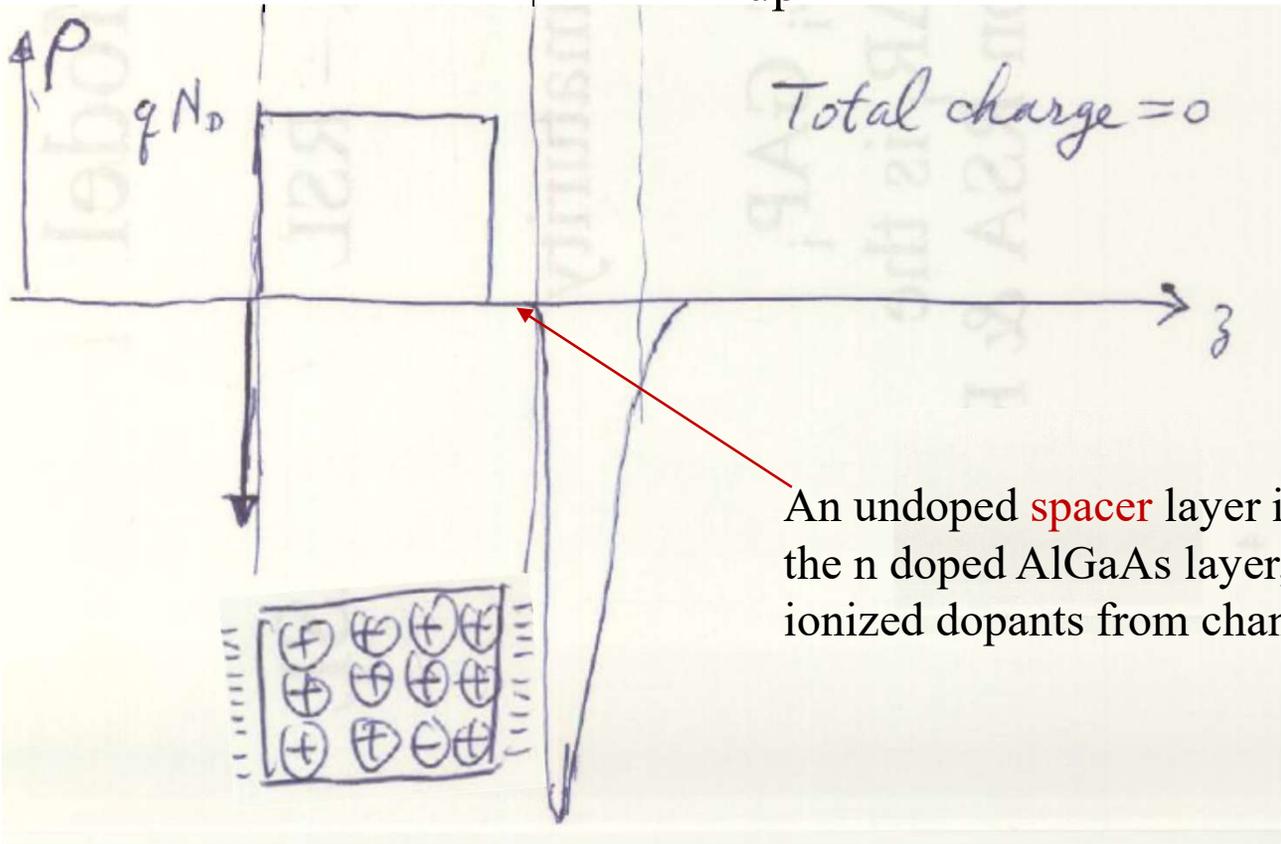




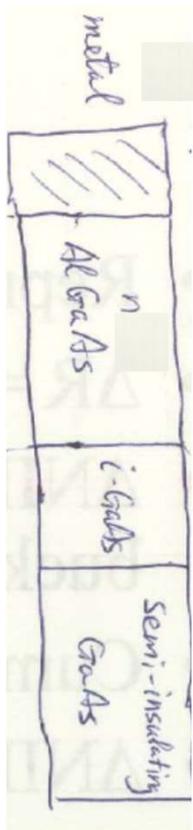
2-dimensional electron gas (2DEG)



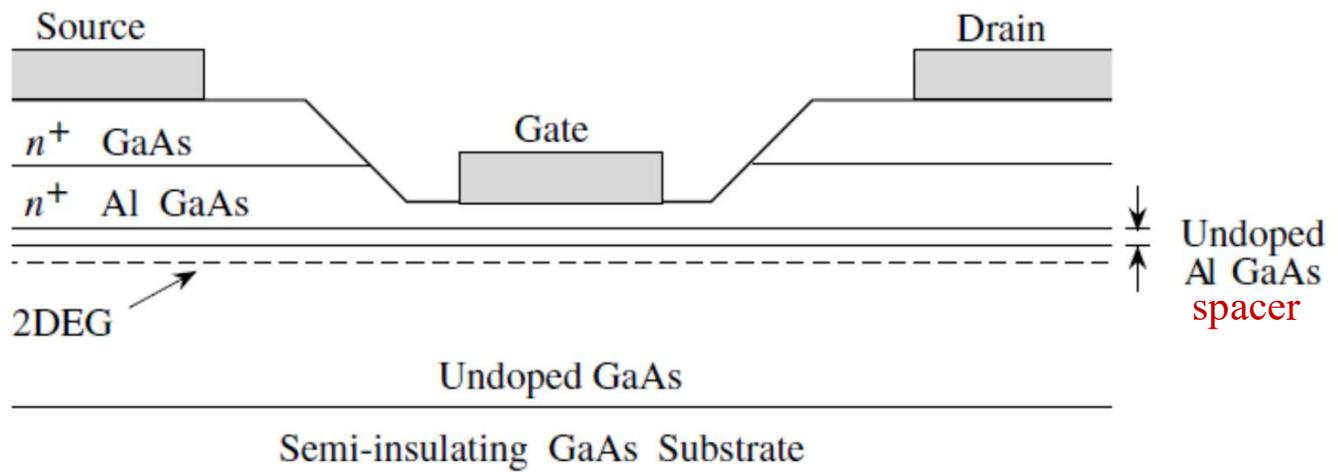
$V_G = 0$ , Fermi levels line up



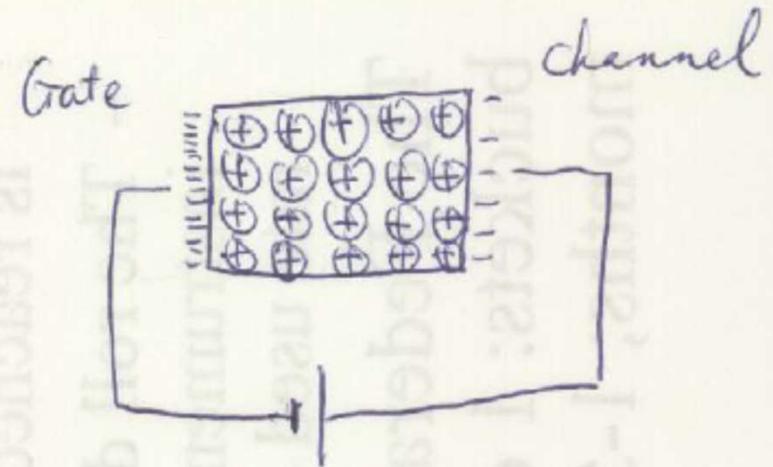
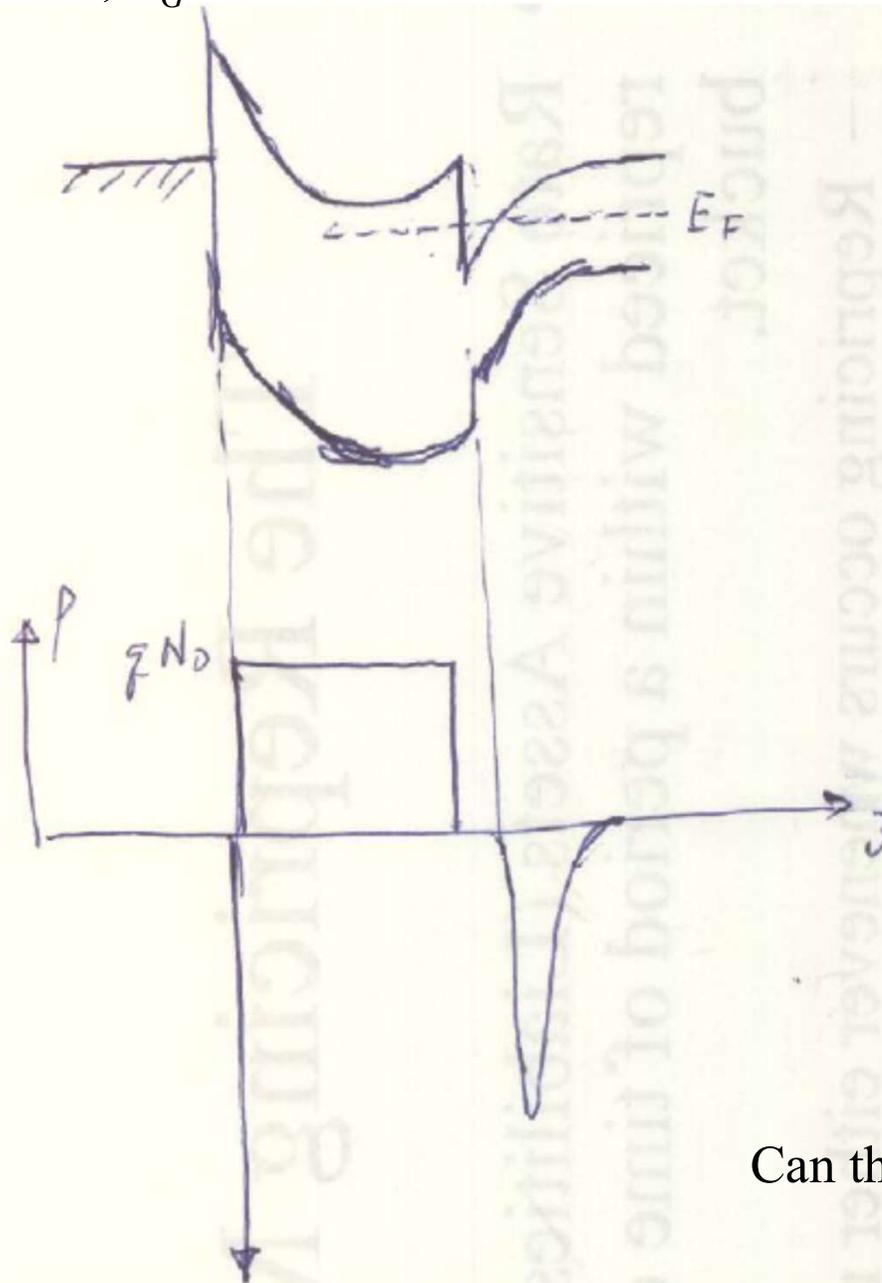
An undoped **spacer** layer is grown before the n doped AlGaAs layer, to separate ionized dopants from channel.



(not to scale)



Now,  $V_G < 0$

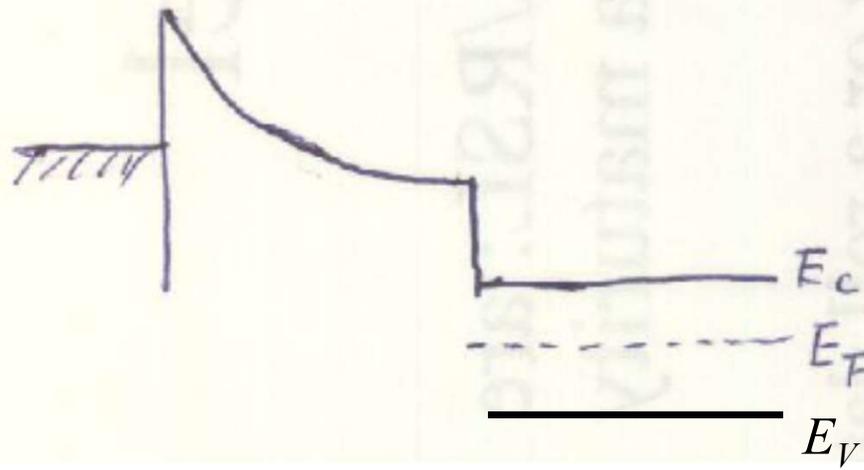


The battery pumps  $e^-$ 's to the gate. Total charge conserves.

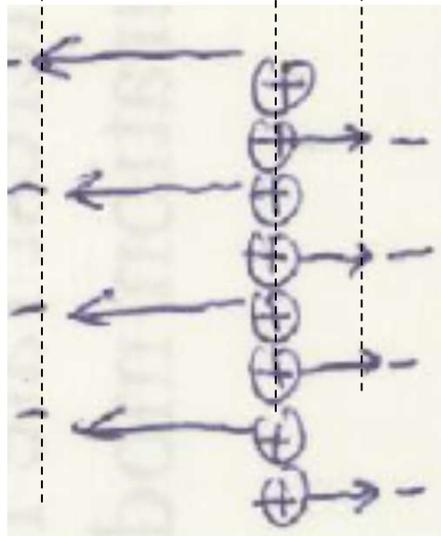
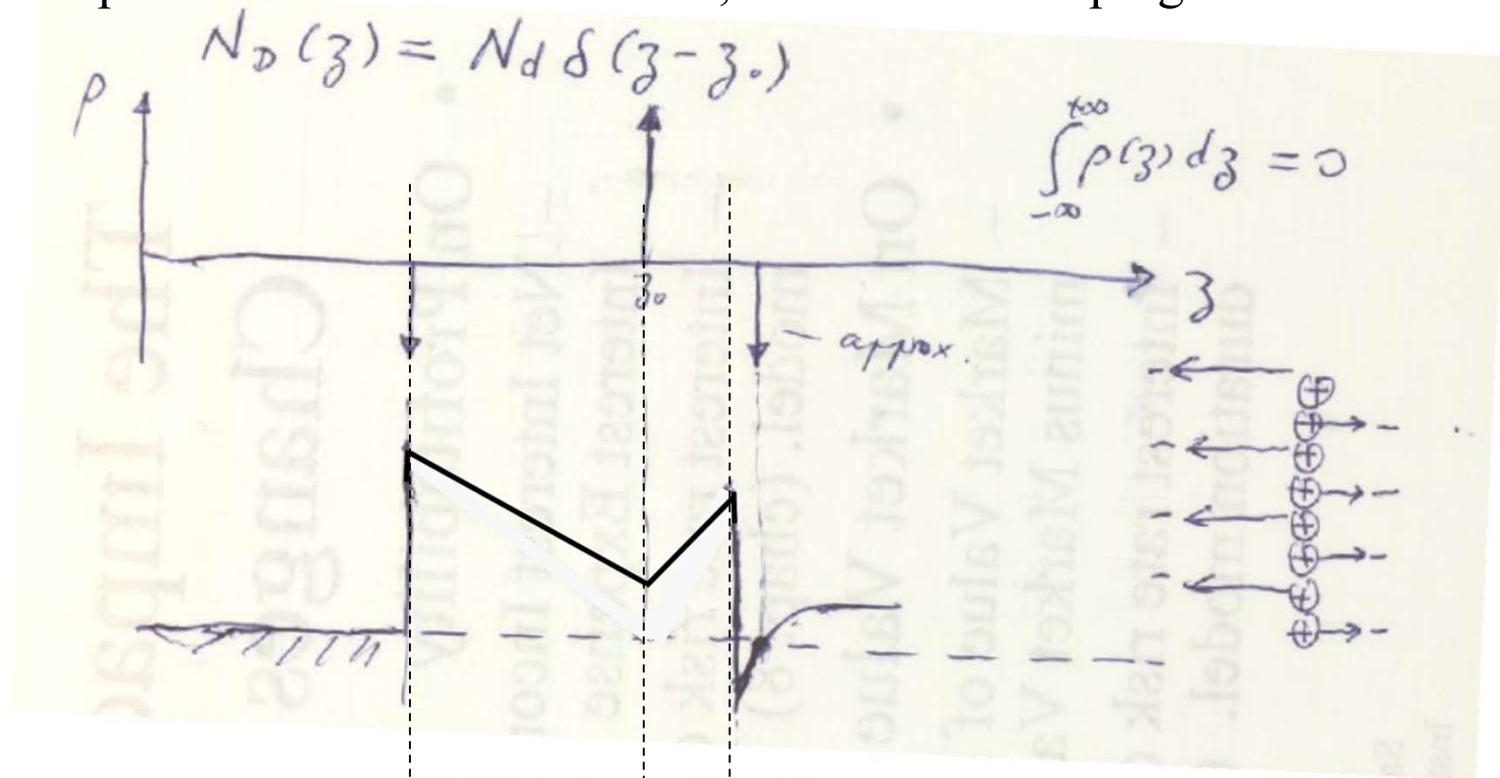
Negative charge (electrons) partition between 2DEG and gate.

Can there be an inverted p channel in AlGaAs?

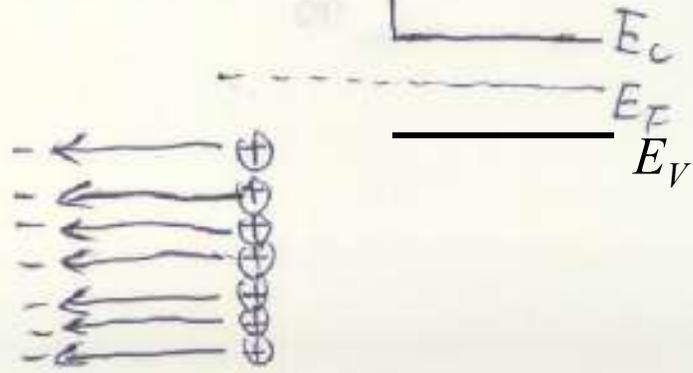
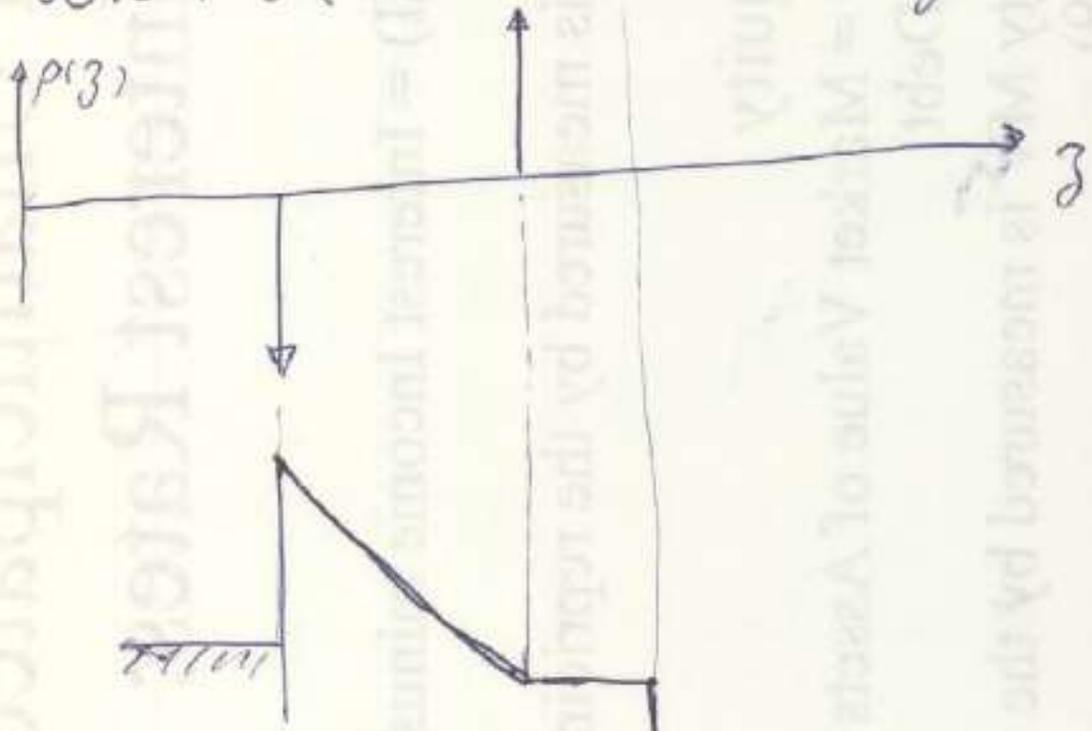
now. more negative  $V_G$ , channel depleted.



To avoid "parasitic channel" in AlGaAs, can do "delta doping"

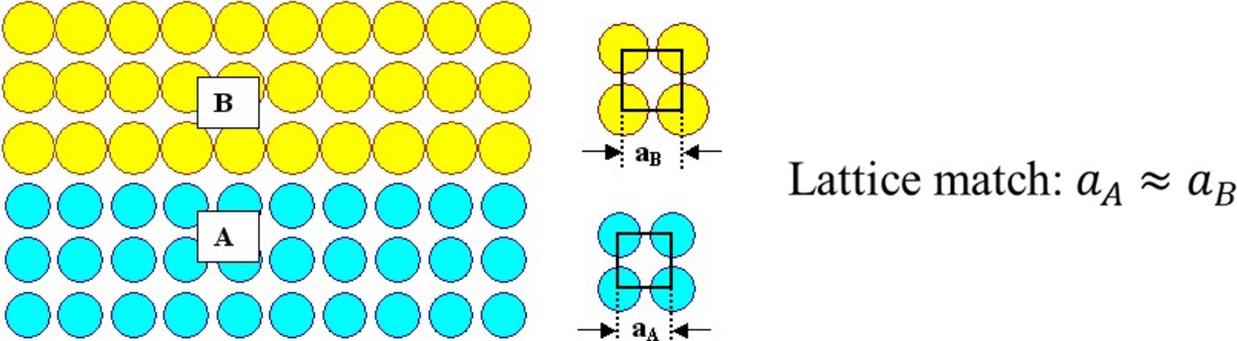


When the channel is totally depleted



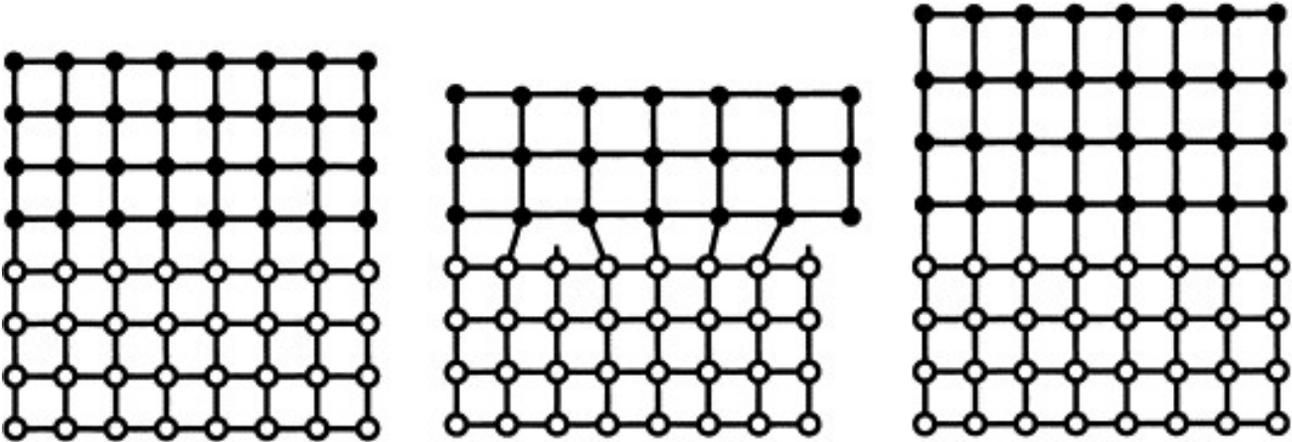
To really understand MODFETs, we need to understand heterojunctions.

- Fabrication of heterostructures: epitaxy



[https://www.tf.uni-kiel.de/matwis/amat/semitech\\_en/kap\\_3/backbone/r3\\_4\\_1.html](https://www.tf.uni-kiel.de/matwis/amat/semitech_en/kap_3/backbone/r3_4_1.html)

(Epitaxy may be homoepitaxy, e.g., undoped GaAs on semi-insulating GaAs in our MODFET example)



(a). Commensurate

(b). Incommensurate, relaxed

(c). Pseudomorphic, with uniaxial dilation

$$a_A \cong a_B$$

<https://www.sciencedirect.com/science/article/pii/S0039602801015254>

III	IV	V
5 B	6 C	7 N
13 Al	14 Si	15 P
31 Ga	32 Ge	33 As
49 In	50 Sn	51 Sb
81 Tl	82 Pb	83 Bi

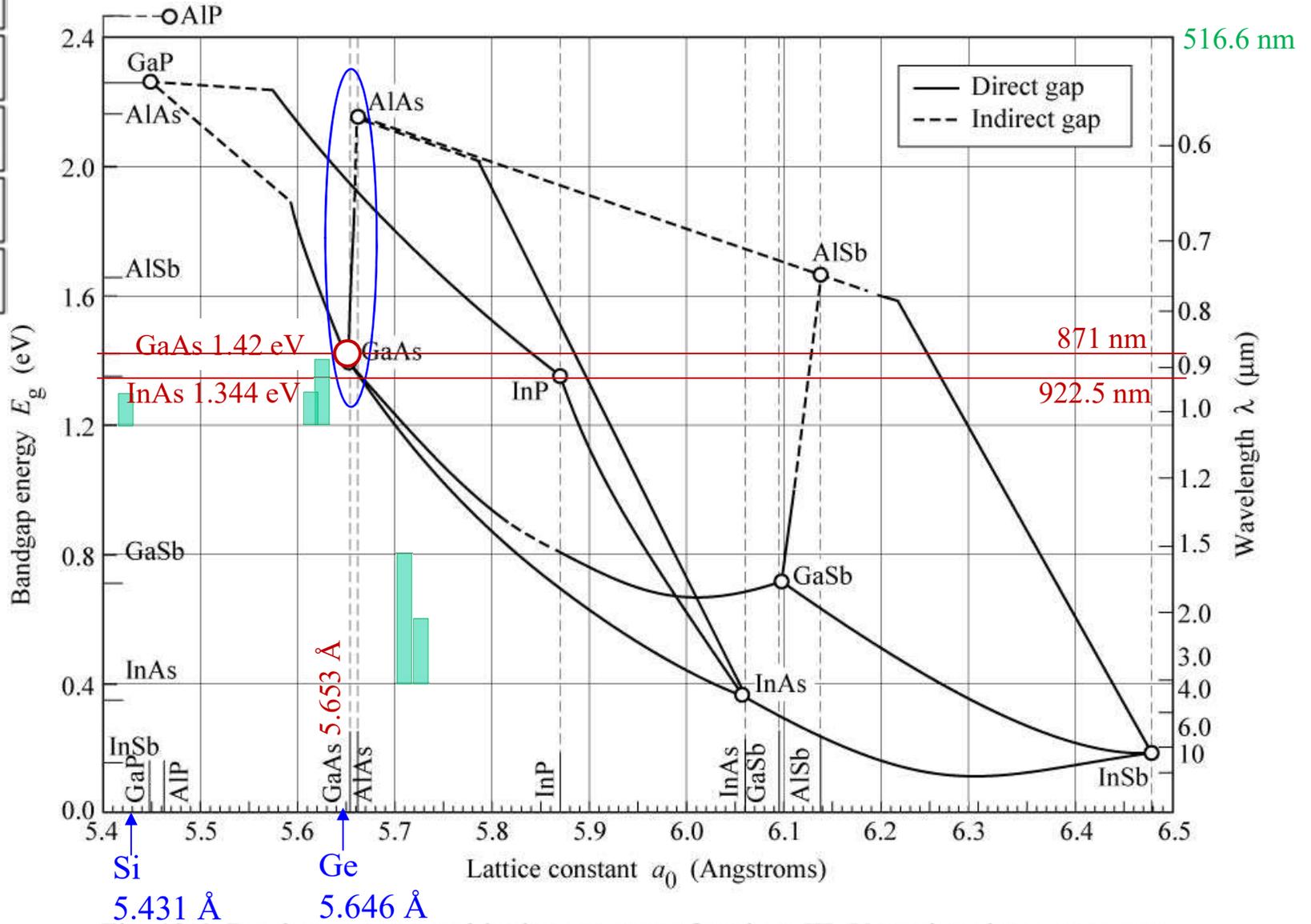


Fig. 12.6. Bandgap energy and lattice constant of various III–V semiconductors at room temperature (adopted from Tien, 1988).

- How do energy levels line up at interfaces?

There are no simple theories.

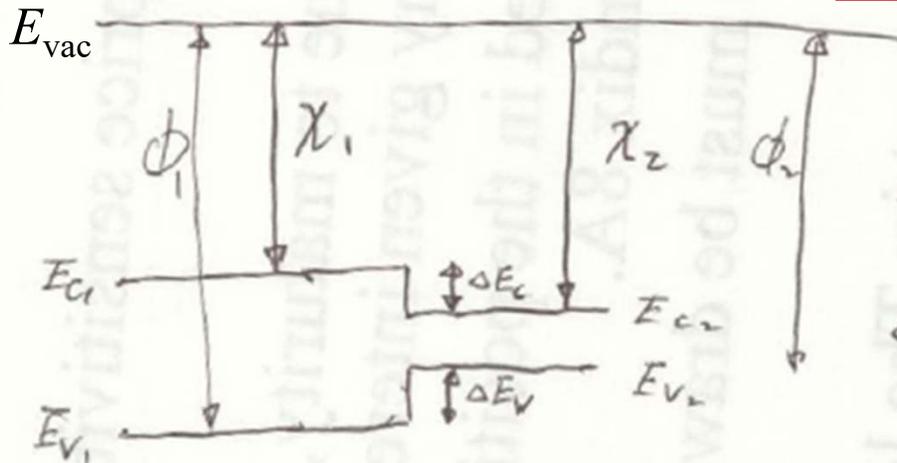
Pretty much every interface (even the same pair of materials but opposite growth order) needs to be experimentally determined.

Recently, first-principles calculations become able to predict.

For simple descriptions, there are two “rules” that are **not** obeyed.

Details (chemistry) of interface ignored, therefore no interface dipoles  $\rightarrow$  no discontinuity in electrostatic potential, or  $E_{vac}$ .

① Electron affinity Rule



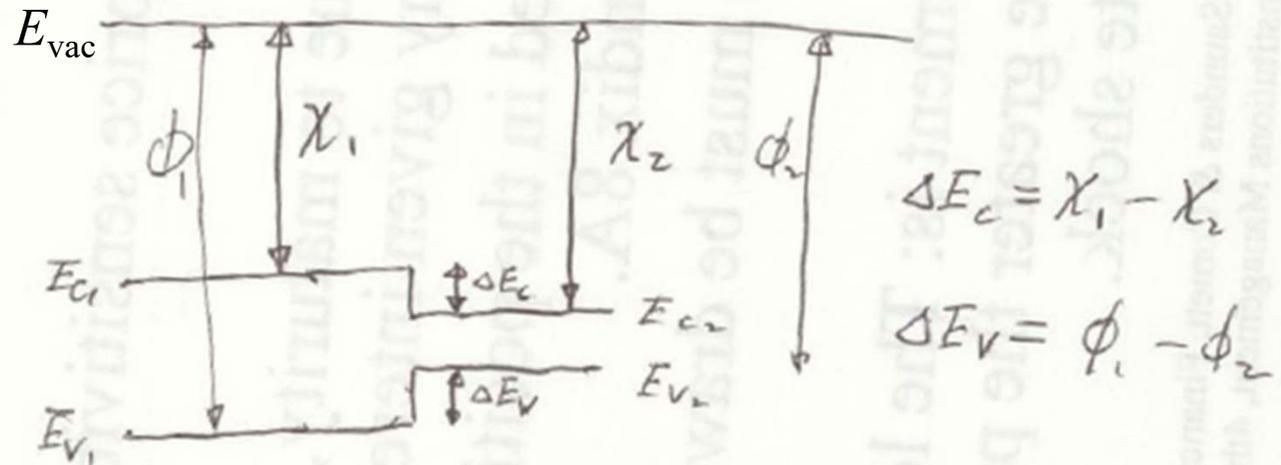
We followed this rule when analyzing the MODFET example.

$$\Delta E_c = \chi_1 - \chi_2$$

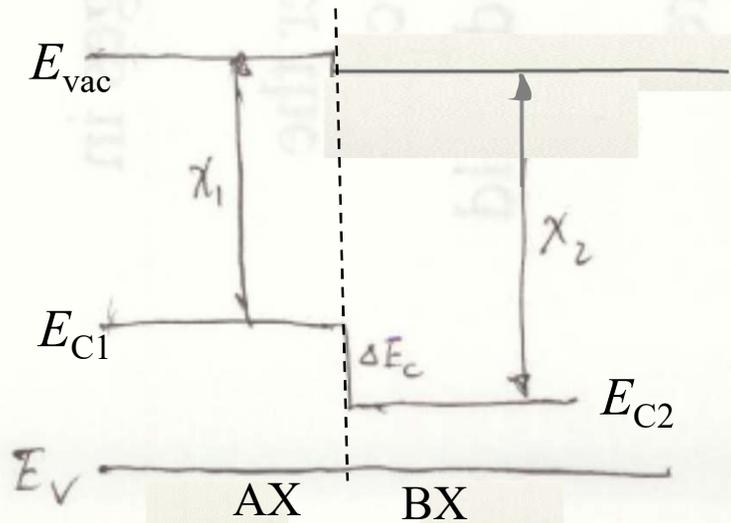
$$\Delta E_v = \phi_1 - \phi_2$$

In this illustration, the horizontal dimension is not meaningful except marking the interface; charge transfer dictates band bending.

## ① Electron affinity Rule



## ② Common Anion Rule



$$\Delta E_v \approx 0$$

$$\Delta E_c \approx \Delta E_g$$

Valence band max largely determined by anion atomic orbitals.

Both "rules" ignore interface dipoles.